

Serial No. 10/795,979

Atty. Docket No. 249/437

Proposed Amendment dated February 15, 2006Reply to Interview Summary mailed February 8, 2006**Proposed Amendment to Claim 21:**

The proposed amendment to claim 21 would recite as follows:

21. (Currently Amended) A method of fabricating a pyroelectric emitter an electron beam lithography apparatus, comprising:  
preparing a pyroelectric plate;  
preparing a patterned mask of a semiconductor material,  
including sequentially forming a semiconductor thin film  
having a predetermined thickness and a resist on a dielectric  
plate having the predetermined thickness, patterning the resist  
in a predetermined pattern, patterning the semiconductor thin  
film using the patterned resist as a mask, and removing the  
patterned resist, the semiconductor material being sufficiently  
thick in desired portions to prevent electrons emitted by the  
pyroelectric plate during heating from being further  
transmitted; [[and]]  
disposing the patterned mask adjacent the surface of the  
pyroelectric plate;  
providing a heating source for heating the pyroelectric  
emitter; and  
providing a pair of magnets disposed beyond the  
pyroelectric emitter and the substrate holder, respectively, to  
control paths of electrons emitted by the pyroelectric emitter.